

Docket Number: 081468-0306525

PATENT APPLICATION

Client Reference: P-1586.010-US

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

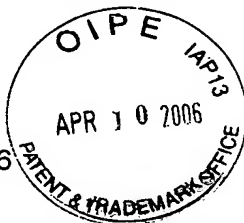
In Re the Application of

JOERI LOF, et al.

Application No.: 10/705,816

Filed: November 12, 2003

For: LITHOGRAPHIC APPARATUS AND DEVICE MANUFACTURING METHOD



Group Art Unit: 2878

Examiner: Lu, Tony W.

Confirmation No.: 5408

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

Sir:

Pursuant to 37 CFR 1.56, the attention of the Patent and Trademark Office is hereby directed to the references listed on the attached PTO-1449. One copy of each non-U.S. reference is attached. It is respectfully requested that the information be expressly considered during the prosecution of this application, and that the references be made of record therein and appear among the "References Cited" on any patent to issue therefrom. Applicant respectfully requests the Examiner return an initialed copy of the enclosed Form PTO-1449 to Applicant with the next Office communication to indicate that the references have been considered, per MPEP § 609.

This Information Disclosure Statement is being filed after the mailing of the first official action on the merits but before the mailing date of a Final Rejection or Notice of Allowance. Please charge Deposit Account 033975 in the amount of \$180.00 in payment of the fee under 37 CFR 1.17(p) pursuant to 37 CFR 1.97(c)(2). Please credit or debit Deposit Account 033975 as needed to ensure consideration of the disclosed information.

Respectfully Submitted,

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Registration Number 42663
Customer Number: 00900

04/11/2006 JAB001 00000000 033975 10705816
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Date: April 10, 2006
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FORM PTO-1449 (modified)
To: U.S. Department of Commerce
(PW FORM PAT-1449)
Patent and Trademark Office



Atty. Dkt. No.	M#	Client Ref.
	306525	P-1586.010-US

**INFORMATION DISCLOSURE STATEMENT
BY APPLICANT**

Applicant:	LOF et al.
Appln. No.	10/705,816
Filing Date:	November 12, 2003
Examiner:	Unknown Tony L.
Group Art Unit:	2882 2078

Date: January 7, 2005 Page 1 of 2

U.S. PATENT DOCUMENTS

Examiner's Initials*		Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
TL	AR	4,390,273	06/1983	LOEBACH et al.	355	125	
TL	BR	6,603,130	08/2003	BISSCHOPS et al.	250	492.1	
TL	CR	6,633,365	10/2003	SUENAGA	355	53	
TL	DR	2002/0163629	11/2002	SWITKES et al.	355	53	
TL	ER	2003/0123040	07/2003	ALMOGY	355	69	
TL	FR	2003/0174408	09/2003	ROSTALSKI et al.	359	842	
TL	GR	2004/0075895 A1	04/2004	LIN	359	380	
TL	HR	2004/0109237 A1	06/2004	EPPLÉ et al.			
TL	IR	6,236,634 B1	05/2001	LEE et al.	369	112	
TL	JR	2002/0020821 A1	02/2002	VAN SANTEN et al.	250	492	
TL	KR	2004/0119954	06/2004	KAWASHIMA et al.	355	30	
TL	LR	2004/0125351	07/2004	KRAUTSCHIK et al.	355	53	

FOREIGN PATENT DOCUMENTS

		Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract		Translation Readily Available	
						Enclosed	No	Enclosed	No
TL	MR	JP 04-305915	10/1992	JAPAN	OZEKI et al.	X			
	NR	JP 04-305917	10/1992	JAPAN	OZEKI et al.	X			
TL	OR	JP 06-124873	05/1994	JAPAN	TAKAHASHI	X		X	
TL	PR	JP 07-220990	08/1995	JAPAN	FUKUDA et al.				
TL	QR	JP 10-228661	08/1998	JAPAN	KUROKAWA	X			
TL	RR	JP 10-255319	09/1998	JAPAN	SUENAGA et al.	X			
TL	SR	JP 10-303114	11/1998	JAPAN	SUWA	X		X	
TL	TR	JP 10-340846	12/1998	JAPAN	KUDO	X		X	
TL	UR	JP 2001-091849	04/2001	JAPAN	AIZAKI et al.	X			
TL	VR	JP 07-132262	05/1995	JAPAN	HIRAKAWA et al.	X			

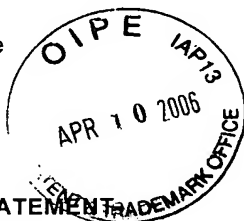
OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

TL	WR	B.J. LIN, "Drivers, Prospects and Challenges for Immersion Lithography", TSMC, Inc., September 2002			
TL	XR	B.J. LIN, "Proximity Printing Through Liquid", IBM Technical Disclosure Bulletin, Vol.20, No. 11B, April 1978, p. 4997			
TL	YR	S. OWA et al., "Update on 193nm immersion exposure tool", Litho Forum, International SEMATECH, Los Angeles, January 27-29, 2004, Slide Nos. 1-51			
TL	ZR	H. HATA, "The Development of Immersion Exposure Tools", Litho Forum, International SEMATECH, Los Angeles, January 27-29, 2004, Slide Nos. 1-22			
TL	AAR	T. MATSUYAMA et al., "Nikon Projection Lens Update", SPIE Microlithography 2004, 5377-65, March, 2004			
	BBR				

Examiner	Date Considered:
	12/2005

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

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Examiner: Lu, Tony W

Group Art Unit: 2878

U.S. PATENT DOCUMENTS

Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
	AR 2005/0052632	03/2005	MIYAJIMA	355	53	
	BR 2005/0219489	10/2006	NEI ET AL.	355	53	
	CR 2005/0200815	09/2005	AKAMATSU	353	53	
	DR					
	ER					

FOREIGN PATENT DOCUMENTS

	Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract		Translation Readily Available	
					Enclosed	No	Enclosed	No
	FR WO 2004/095135	11/2004	PCT	NOVAK	X			
	GR WO 2004/102646	11/2004	PCT	ISHII	X			
	HR WO 2005/031799	04/2005	PCT	NISHINAGA ET AL.	X			
	IR WO 2005/036624	04/2005	PCT	YASUDA ET AL.	X			
	JR WO 2005/074014	08/2005	PCT	SHIBAZAKI	X			
	KR							
	LR							

OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

MR	European Search Report for EP Application No. 03257072.3, dated June 23, 2005.			
NR				
OR				

Examiner

Date Considered:

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